

# Électrodes à cristaux bidimensionnelles pour micro/nano-résonateurs piézoélectriques à haut facteur de qualité

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# Outline

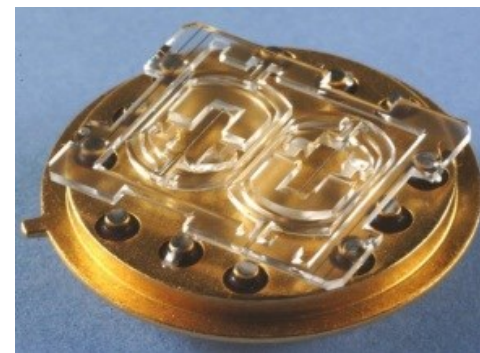
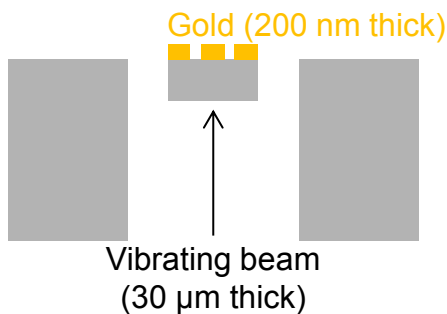
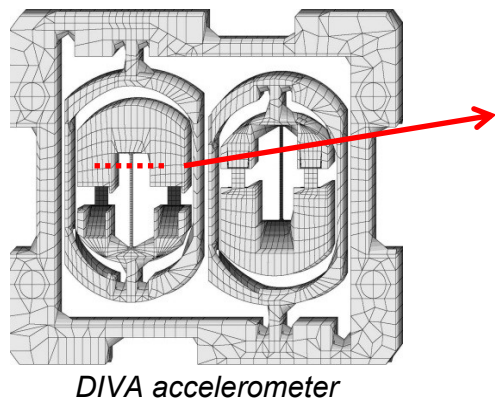
1. Introduction
2. Graphene transfer
3. Application to quartz resonators
  - a. Direct transfer and patterning
  - b. Conductive ink deposition
  - c. Ion etching of graphene
4. Conclusion

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# 1. Introduction

## Graphene electrodes for MEMS resonators



DIVA accelerometer on its packaging

- Main damping mechanisms for flexural beams:

$$Q_{TED} \sim 560\,000 \text{ @ } 22\text{kHz}$$

$$Q_{visc} \sim 140\,000$$

- Viscoelastic losses proportional to the electrode thickness:



$$\frac{1}{Q_{visc}} = \omega \frac{\eta_{electrode} t_{electrode}}{E_{cristal} t_{cristal}}$$

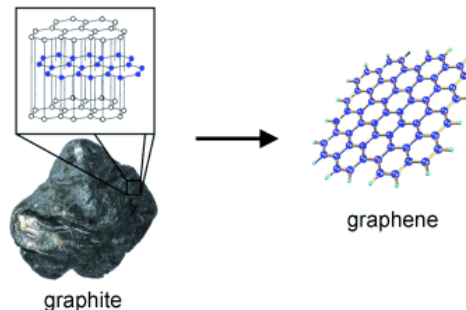
→ Aim: replace gold by a thinner material onto the vibrating region

# 1. Introduction

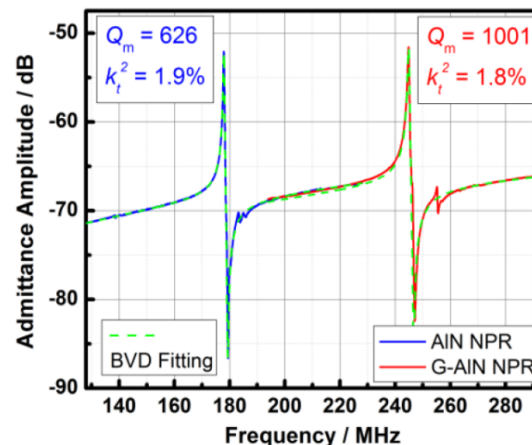
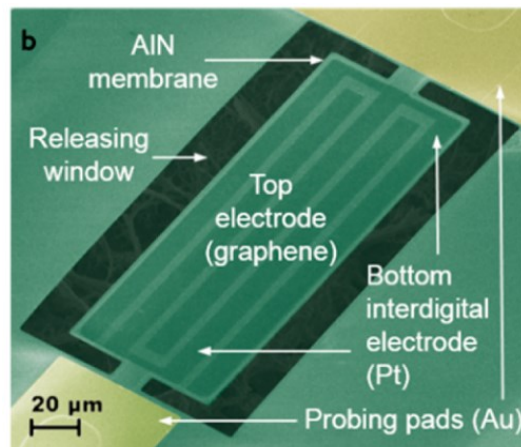
## State of the art

### Graphene:

- 2D crystal, derivative of graphite
- One atom thick layer of C atoms
- Low intrinsic viscosity (?)



### Aluminum nitride (AlN) resonator with a graphene top electrode



Z. Qian et al., *Proceedings of the 2013 IEEE International Frequency Control Symposium*, pp. 559-561.

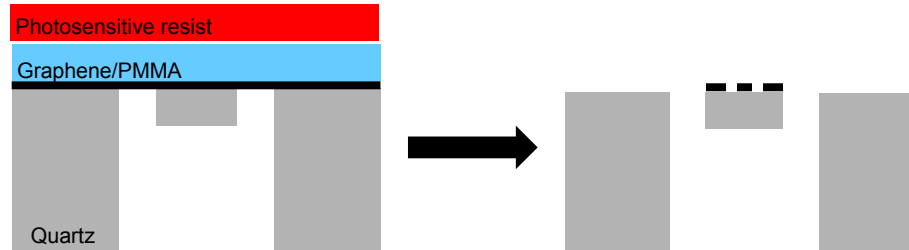
- ✓ Higher resonance frequency and improved quality factor
- ✗ Bottom platinum electrode

# 1. Introduction

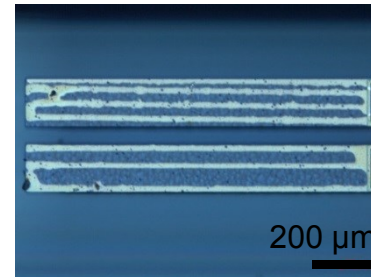
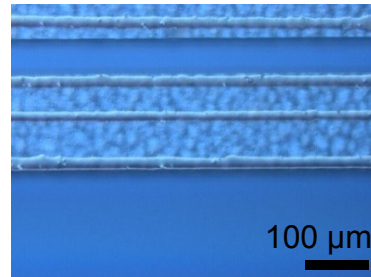
## Thesis objectives

- Different strategies for **less intrusive electrodes** onto the vibrating parts of quartz resonators:

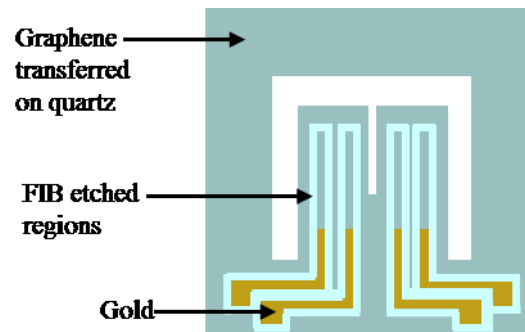
- **Direct transfer and patterning on resonators**



- **Conductive inks**



- **Focused Ion Beam (FIB) etching of graphene**



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# 2. Graphene transfer and patterning

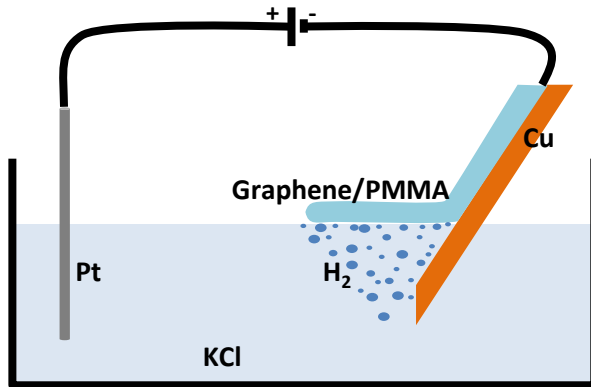
## Transfer techniques

- Graphene monolayer grown by Chemical Vapor Deposition (CVD) on a copper substrate
- Transfer = graphene separation from copper + transfer on target substrate

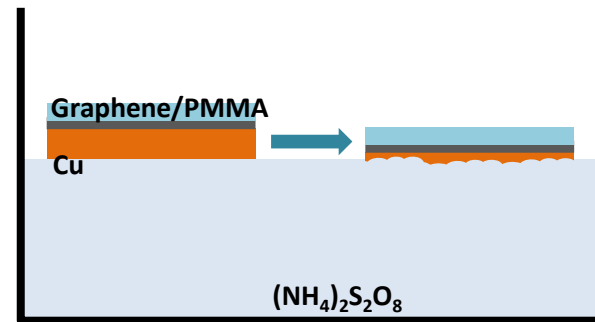


Spin coating of PMMA resist on top of graphene for mechanical support during the transfer process

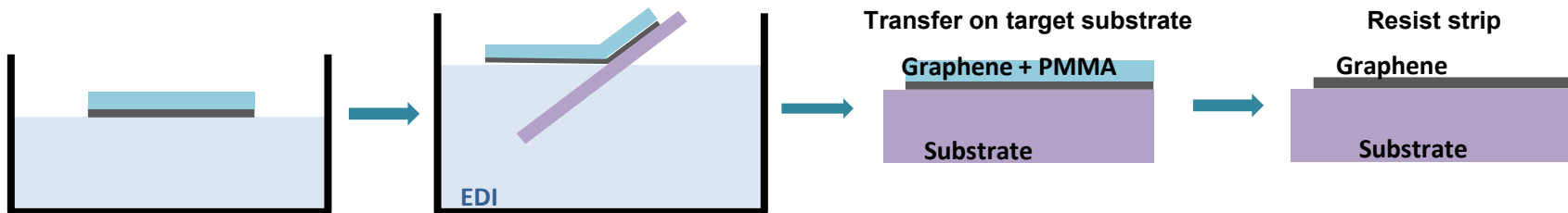
### Electrochemical delamination



### Copper etching



### Transfer

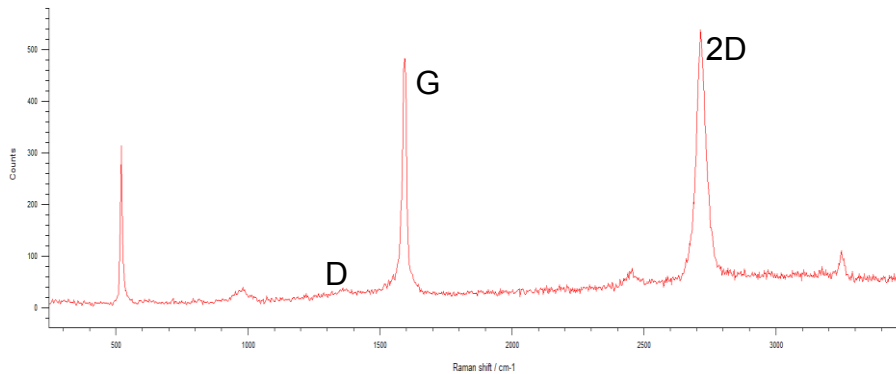
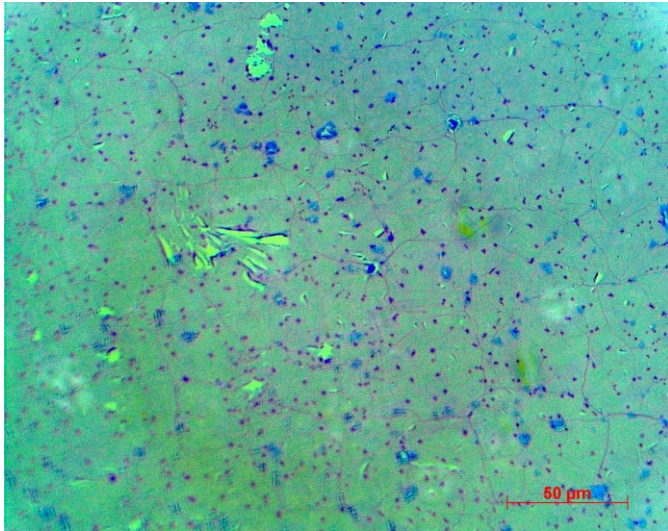




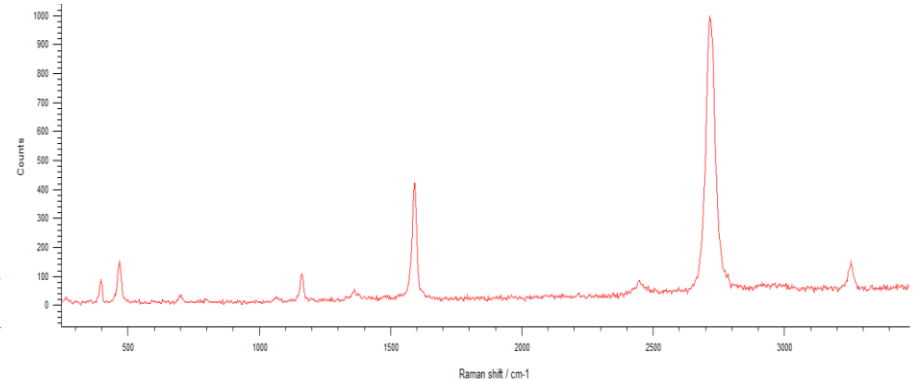
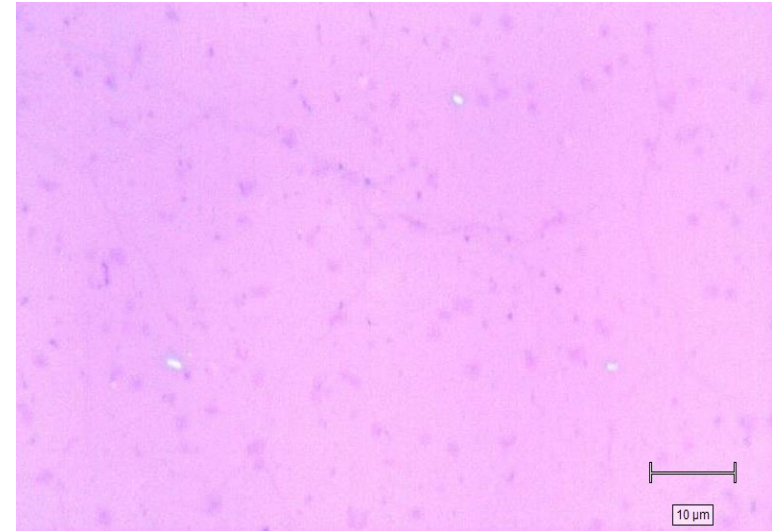
## 2. Graphene transfer and patterning

### Transfer techniques – Graphene characterization

#### Electrochemical delamination



#### Copper etching



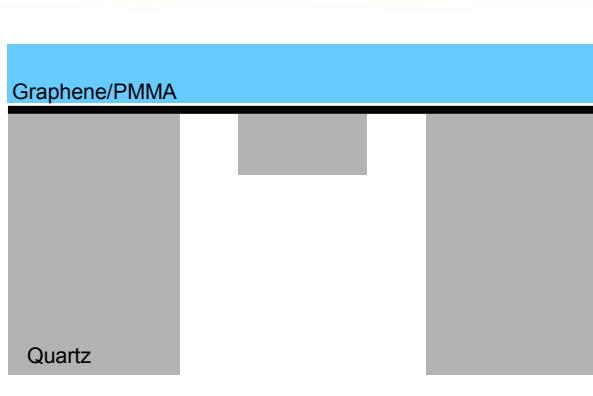
- ✓ Low density of defects for both processes
- ✓ No luminescence (no resist residue)
- ✓ Less cracks with copper etching

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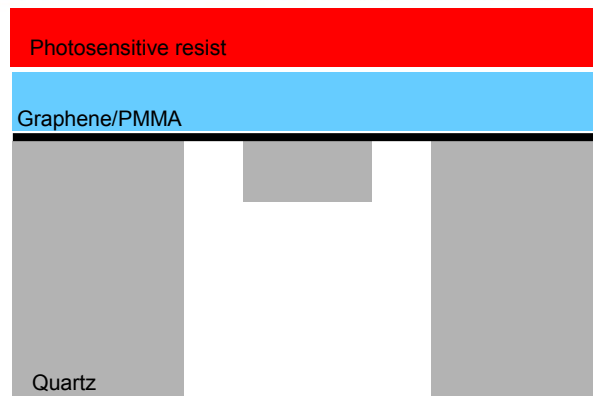
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# 3. Application to quartz resonators

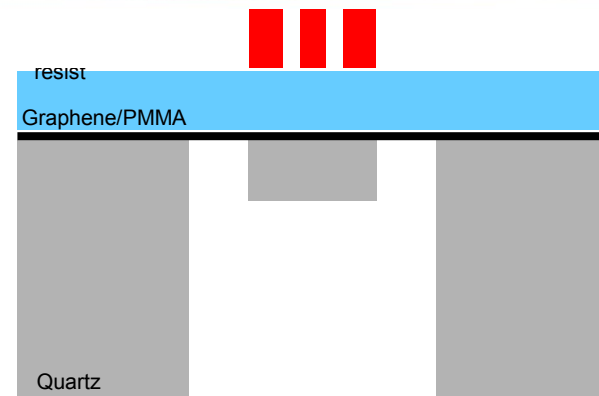
## a. Direct transfer and patterning



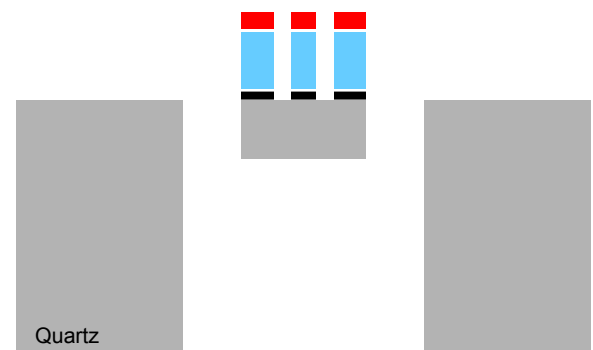
1. Graphene/PMMA transfer



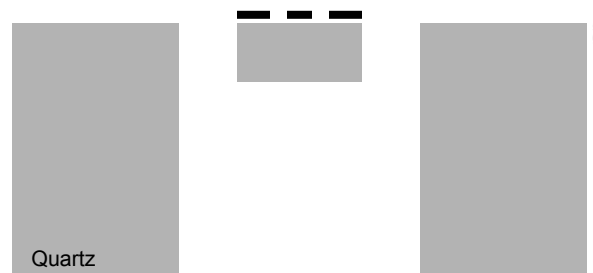
2. Spin coating of photoresist



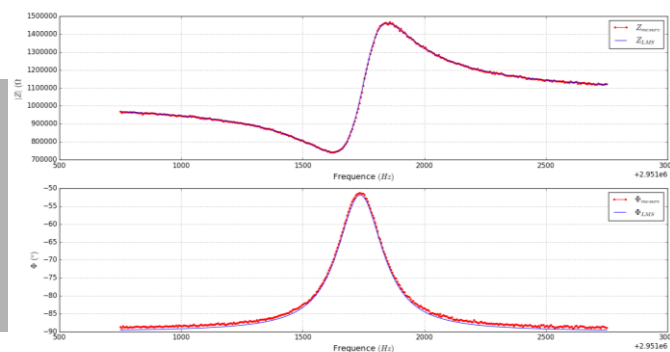
3. Exposure and development



4. Plasma etching



5. Resists dissolution



ARQOMM →  $Q = 14\ 000$  @  $2.9\ \text{MHz}$   
 $7\ 000$  with gold electrodes  
**✓ Enhancement of Q at atmospheric pressure**

### Future work:

- Process optimization to obtain continuous electrodes
- Characterization under vacuum

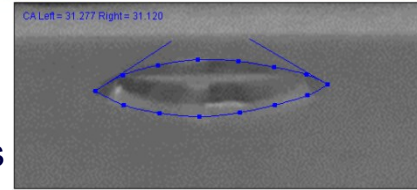
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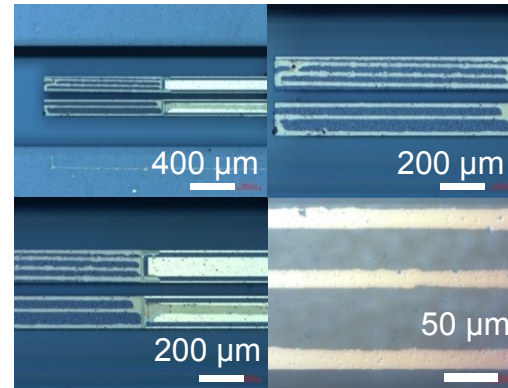
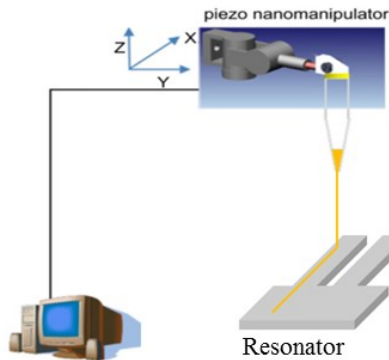
# 3. Application to quartz resonators

## b. Conductive ink deposition – Gold nanoink

- Collaboration with Gilgueng Hwang (C2N)
- Wettability of quartz resonators after the fabrication process



Contact angle left: 31,3°  
Contact angle right: 31,1°  
→ hydrophilic



Gold nanoparticles between 2 and 4 nm in diameter  
✓ Fine lateral resolution (< 20 μm)

- Gold nanoparticles electrodes on a Vibrating Inertial Gyro (VIG)

	Gold nanoparticles electrodes (~100 nm)		Evaporated gold electrodes (200 nm)	
	Frequency (Hz)	Quality factor	Frequency (Hz)	Quality factor
Drive mode	21 825	144 640	22 387 (+/-0.2%)	115 000 (+/-5%)
Sense mode	22 889	146 850	23 267 (+/-1.5%)	137 000 (+/-5%)

- ✓ No significant shift in resonance frequency
- ✓ **Enhancement of Q** compared to standard gyros
- $Q_{drive}$ : + 26%
- $Q_{sense}$ : + 6% (limited by the broken decoupling frame?)
- Promising first results

Further work:

- Gold nanoparticles electrodes < 100nm thick
- Graphene inks

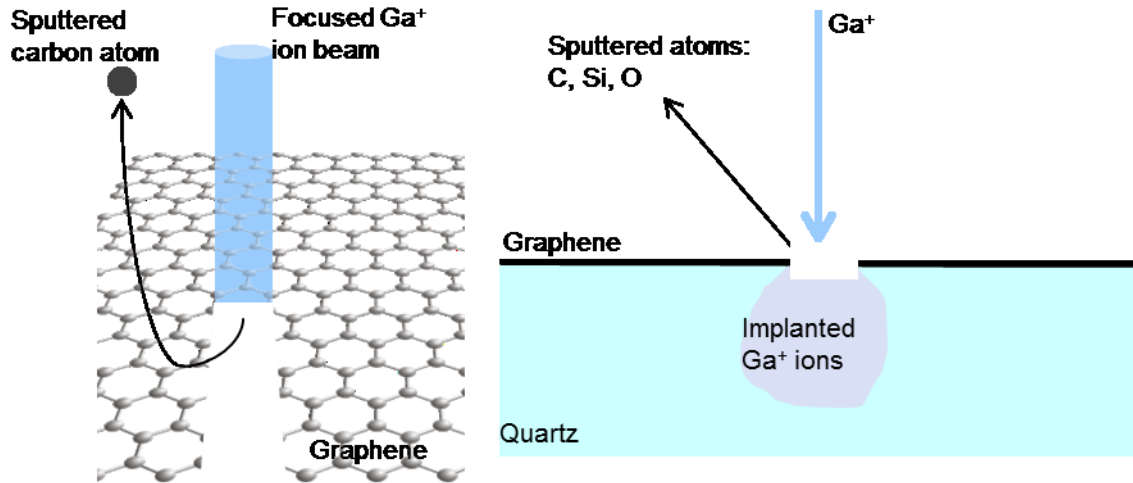
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# 3. Application to quartz resonators

## c. Etching of the graphene electrodes on a VIG

- Etching of graphene by Focused Ion Beam (FIB)



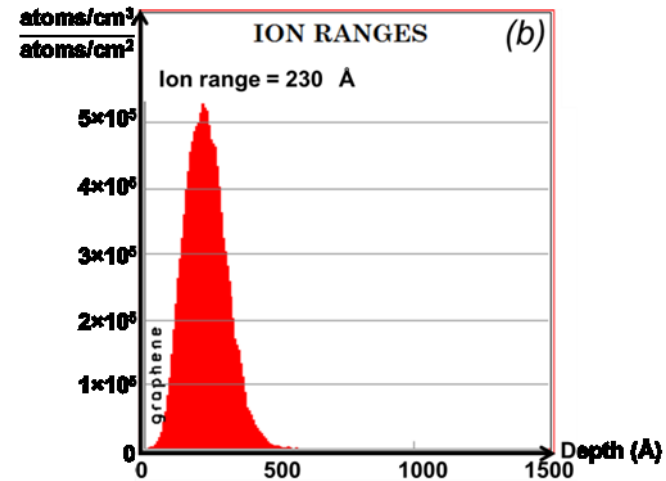
- Stopping and Range Ions in Matter (SRIM) simulation of 30 keV  $\text{Ga}^+$  ion tracks into a monolayer of graphene on top of a quartz substrate

Normal projected range = **23 nm**

Lateral projected range = **5 nm**

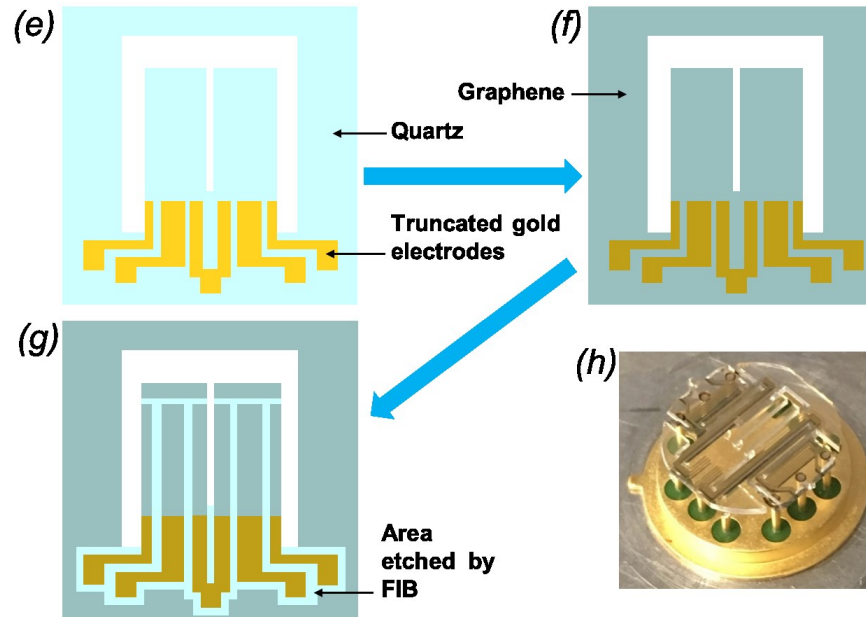
Quartz thickness etched by FIB ~ **3 nm**

→ **Negligible compared to the normal projected range**



### 3. Application to quartz resonators

#### c. Etching of the graphene electrodes on a VIG



	Graphene electrodes		Gold electrodes	
	$f_{\text{resonance}}$ (Hz)	Q	$f_{\text{resonance}}$ (Hz)	Q
Drive mode	22 031	46 000	22 387 (+/- 0.2%)	115 000 (+/- 5%)
Sense mode	23 157	54 000	23 267 (+/- 1.5%)	137 000 (+/- 5%)

- ✓ No significant shift in resonance frequency
- ✗ **Degradation of Q** compared to standard gyros  $Q = 2.5 \times Q_{\text{FIB}}$



# 3. Application to quartz resonators

## c. Etching of the graphene electrodes on a VIG

**Degradation of Q by a factor 2.5**

Hypothesis:

- Intrinsic losses at the **graphene/quartz interface**

	Graphene	Gold electrodes
Sense mode	160 000 (+/-6%)	137 000 (+/- 5%)

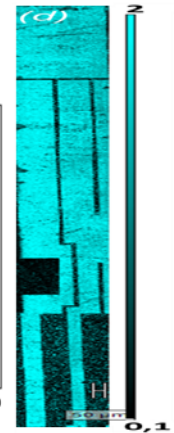
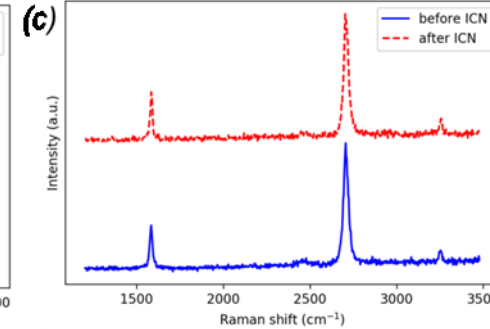
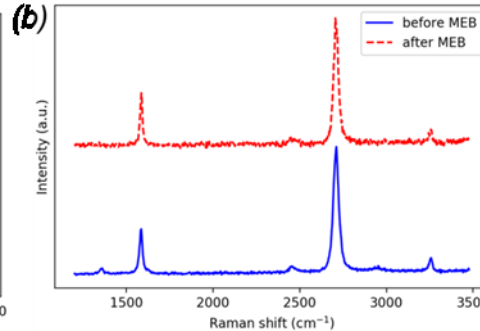
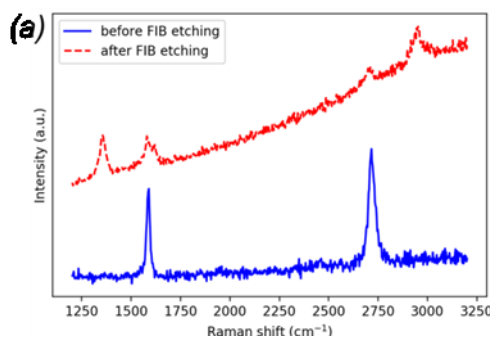
✓ **Improvement of Q with graphene**

- **Quartz amorphization** through ion implantation

	Q before FIB	Q after FIB
Drive mode	112 000	105 000
Sense mode	124 000	111 000

Slight decreasing of Q attributed to the dissipation through redepositing of sputtered material

- **Graphene damage** during electron/ion beam irradiation



- ✗ **Characteristic peaks of defects**
- ✗ **High and homogeneous I(D)/I(G) ratio**
- ✓ **No graphene degradation with electron beam irradiation**

**Ion beam damage ?**

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## 4. Conclusion

- ❑ Réalisation d'un **gyromètre vibrant avec électrodes en graphène par gravure FIB**
- ❑ Caractérisations électriques : **dégradation du facteur de qualité** avec les électrodes en graphène
  - ❑ Effet de la dégradation du graphène et/ou dépôt de carbone amorphe par le faisceau d'électron? → observation MEB de résonateurs avec ou sans graphène dans différentes conditions (faisceau d'électrons focalisé ou nuage d'électrons, avec ou sans doigt froid) → **pas de dégradation**
  - ❑ Amorphisation du quartz? → simili gravure FIB sur dispositif avec électrodes en or complètes et mesure de l'amortissement avant/après gravure → **légère dégradation due au phénomène de redéposition**
  - ❑ Pertes à l'interface graphène/quartz? → mesure de vibrométrie → Q avec graphène autour de 160 000
  - ❑ **Dégradation attribuée au faisceau d'ions → réduction du courant d'ions**
  
- ❑ Transfert et mise en forme du graphène sur résonateur usiné : **procédé de transfert + photolithographie**
  - ❑ Mesures à pression atmosphériques encourageantes sur des ARQOMM : **amélioration du Q d'un facteur 2**
  - ❑ Mesures sous vide en cours
  
- ❑ Étude de l'amortissement de **couches minces par dépôt d'encre conductrices** sur résonateurs : VIG avec électrodes en nanoparticules d'or → **augmentation du facteur de qualité**
  - ❑ Dépôts d'encre graphène/CNT sur résonateurs prévus

**Merci de votre attention**